

(19) (KR)
(12) (B1)

(51) 。 Int. Cl.⁶
H01L 23/28

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(11)
(24)

2003 06 19
10-0388287
2003 06 07

(21) 10-1999-0020938
(22) 1999 06 07

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2001-0001597
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(73) 957

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(54)

r level) (waf
d ling) (han
가 (warpage) ; 가
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; ; ;

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2a	2h	
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2;	3;	
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10;	11;	
12;	13;	
14;	15;	
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40;	50;	
62;		64;
66;	70;	

(wafer level)
(handling)

(warping)

(back grinding)

(saw

ing)

(chip crack)

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6.

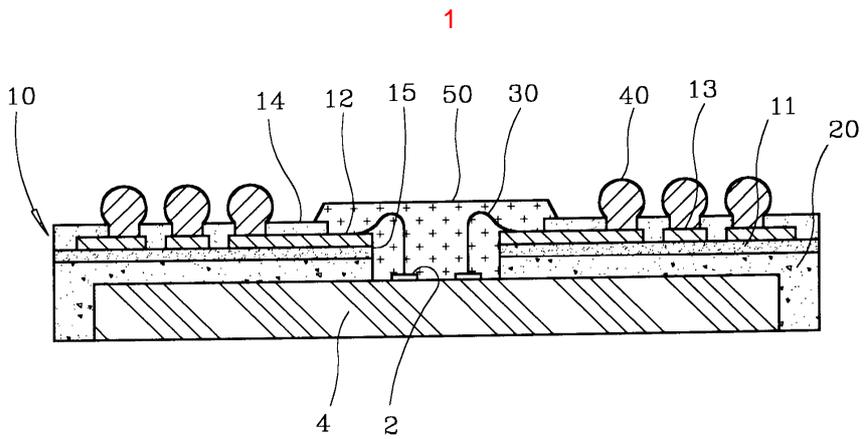
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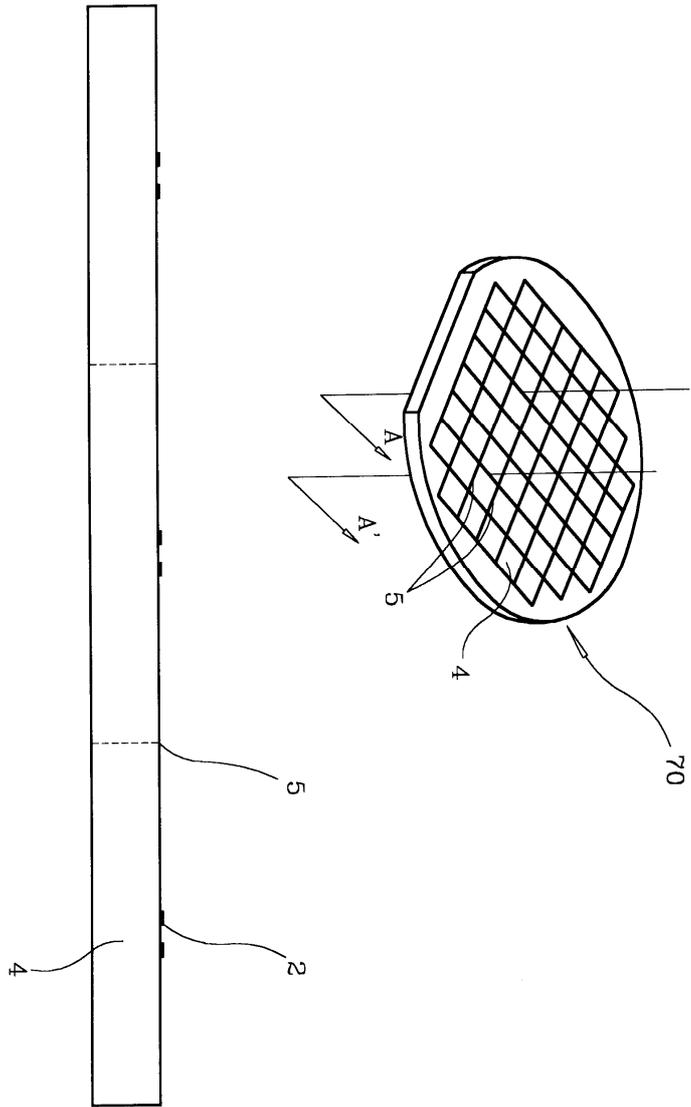
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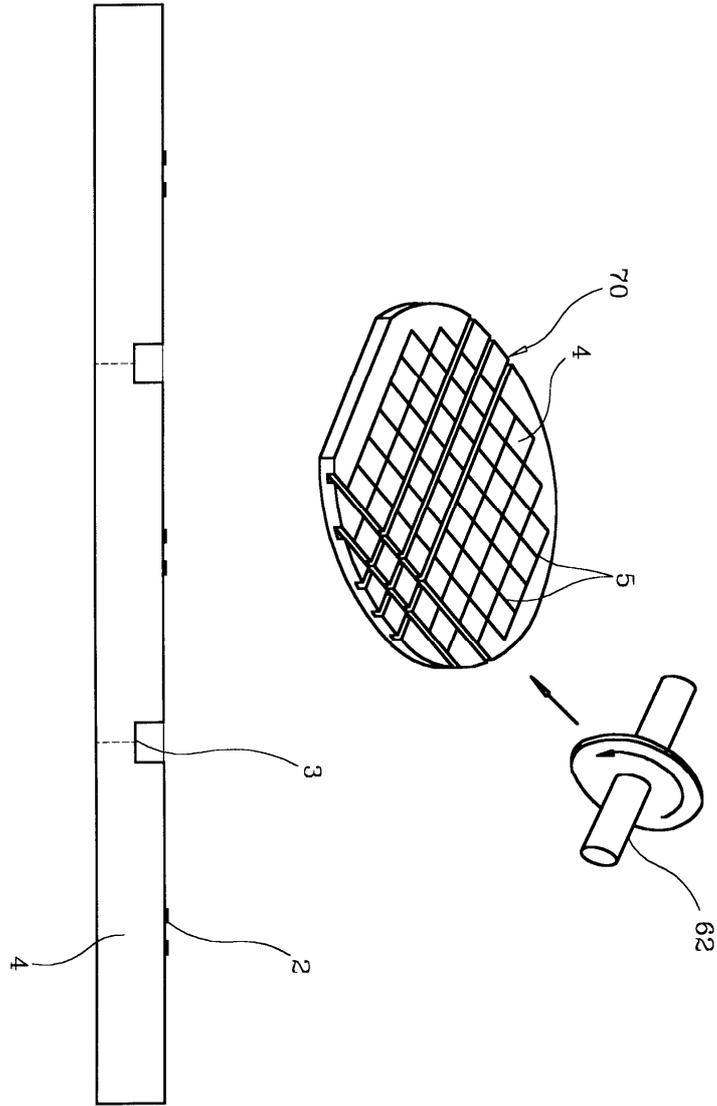
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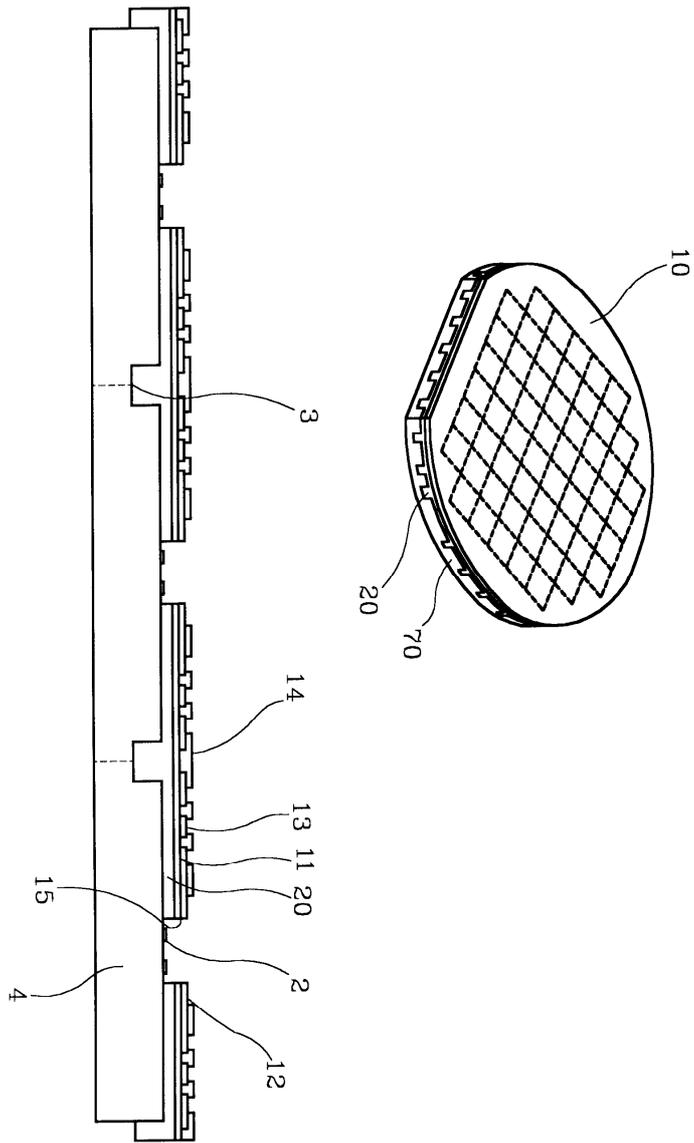
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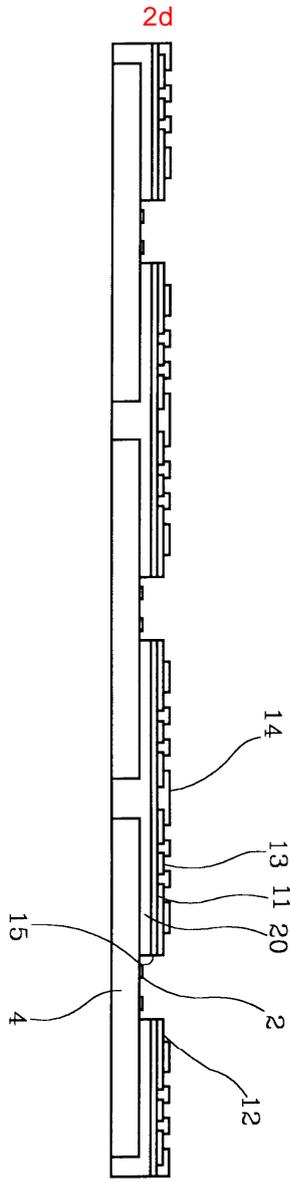


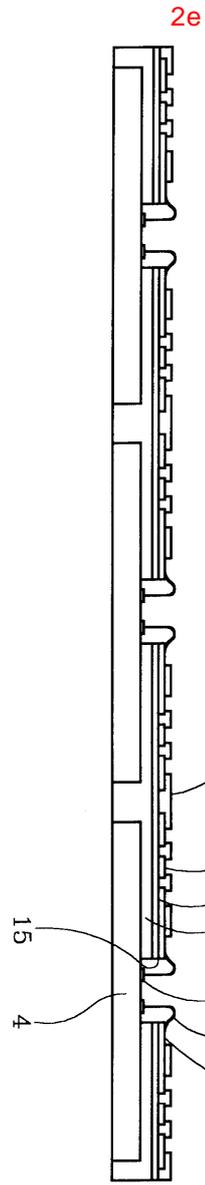
2b

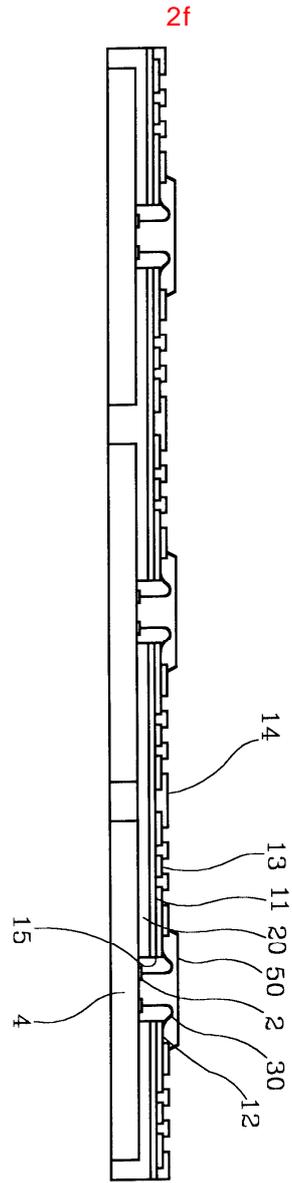


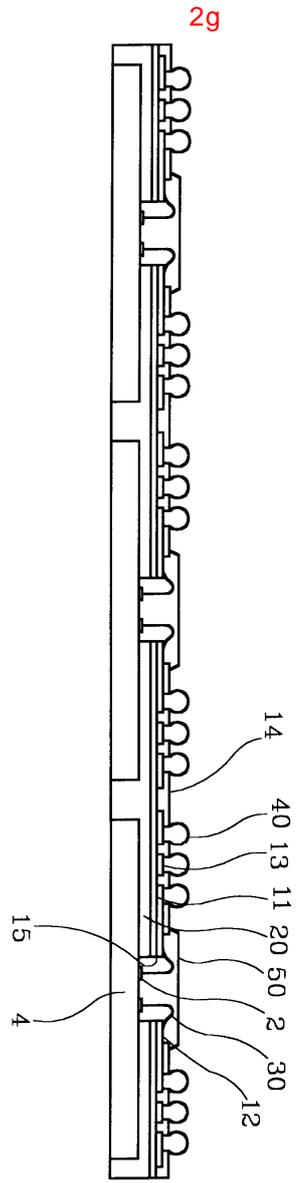
2c











2h

